

AR-U 4030 – run sheet

Allresist

nanyte.com/photoresists/ar-u-4030 · last updated 2026-07-26

Thickness: 1.8–2.5 μm

Softbake: 90 °C · 60 s · hotplate

Exposure dose: 42 mJ/cm²

Post-exposure bake: 115 °C · 4 min

Flood exposure: 74 mJ/cm²

Develop: Developer AR 300-35 · Dilution 4:3 · Time 60 s · Rinse
DI-H₂O, 30 s · Method puddle